ZnO Functionalization of Multi-walled Carbon Nanotubes for Methane Sensing at Single PPM Concentration Levels

<u>Md Humayun</u>¹, R. Divan², L. Stan², A. Gupta³, D. Rosenmann², L. Gundel⁴, P. A. Solomon⁵, I. Paprotny¹

¹University of Illinois at Chicago, Chicago, IL 60607, ²Center for Nanoscale Materials, Argonne National Laboratory, Argonne Il 60439, ³Illinois Mathematics and Science Academy, Aurora, Il 60506, ⁴Lawrence Berkeley National Laboratory, Berkeley, CA 94720, ⁵U. S. Environmental Protection Agency, Las Vegas, NV 89199 mhumay2@uic.edu

Bare carbon nanotubes (CNTs) are insensitive towards most target gases due to poor bonding between the chemically inert graphitic surface and different compounds they are exposed to. For practical applications, the functionalization of CNTs is required and, by introducing surface pre-treatments, their efficiency is enhanced making it possible to produce highly sensitive CNT chemiresistorbased sensors.

Due to the energetically favorable electron transport in ZnO-MWCNT junctions¹, compared with previously reported Pd-MWCNT², we have applied ZnO as the functionalizing material for surface pre-treated multi-walled CNTs (MWCNTs). ZnO was deposited on O₂ plasma and UV O₃ pre-treated MWCNTs using diethylzinc as the precursor (Arradiance Gemstar ALD tool at 175/200/225^oC). The green laser Raman spectroscopy of the ZnO-MWCNT shows that the D, G', G band peaks of the CNTs are preserved, while additional Raman peaks originating from the ZnO layer appeared (Fig. 1). Furthermore, as the ALD process temperature was increased, the ZnO peaks became stronger, suggesting that ZnO deposited on top of the MWCNTs at higher temperatures during the ALD process improves the crystalline quality of the devices. This result was confirmed by energy-dispersive x-ray spectroscopy (EDS) using a scanning electron microscope (SEM) (Fig. 2).

The sensor response $((R_{methane}-R_{air})/R_{air}=\Delta R/R_{air})$ was measured inside a test chamber where CH₄ in air calibration mixtures were introduced as the concentration was continuously monitored using a reference CH₄ detector (Fig. 3). Our novel ZnO-MWCNT methane sensor is capable of detecting a 2 ppm concentration of methane in air at room temperature, the best reported sensitivity for CNT-based methane sensors to this date.

¹ H. Zhang , N. Du , B. Chen , D. Li, & D. Yang, *Science of Advanced Materials* 2009 , *1*(1), 13-17.

² Y. Lu, J. Li, J. Han, H. T. Ng, C. Binder, C. Partridge, & M. Meyyappan, *Chemical Physics Letters* 2004, *391*(4), 344-348.

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Figure 1: Raman spectra obtained from the ZnO-MWCNT samples after ALD at (a) 225 0 C, (b) 200 0 C and (c) 175 0 C. The peaks at 200.6 cm⁻¹, 429.13 cm⁻¹, 572.2 cm⁻¹ and 329.44 cm⁻¹ correspond to 2E₂^{low}, E₂^{high}, A₁ (LO), E₂^{high} - E₂^{low} modes of ZnO, respectively, thus suggesting samples with good crystalline quality.



Figure 2: (a) SEM image of MWCNTs confined between two Au electrodes. (b) SEM and EDS results obtained from a UV-O₃ treated ZnO functionalized MWCNT sample fabricated by ALD at 225 ^oC. The Zn (L-Line) peak was only found on the MWCNTs (stronger on brighter point 1, weaker on less brighter point 2). Point 3, which is on the SiO₂ substrate, did not show a Zn signal.



Figure 3: (a) Room temperature sensor response ($\Delta R/R$) for ZnO- plasma pretreated MWCNT, ZnO-untreated MWCNT and plasma treated but not ZnO functionalized MWCNT sensor. (b) Time dependence of the sensor response when exposed to a CH₄ concentration of 2 ppm.

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